

WP10 – CSIC report



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3rd AIDAinnova annual meeting, Catania, March 2024



This project has received funding from the European Union's Horizon 2020 research and innovation programme under grant agreement No 101004761.

- detector R&D embedded in the global R&D landscape

Future Projects Timeline

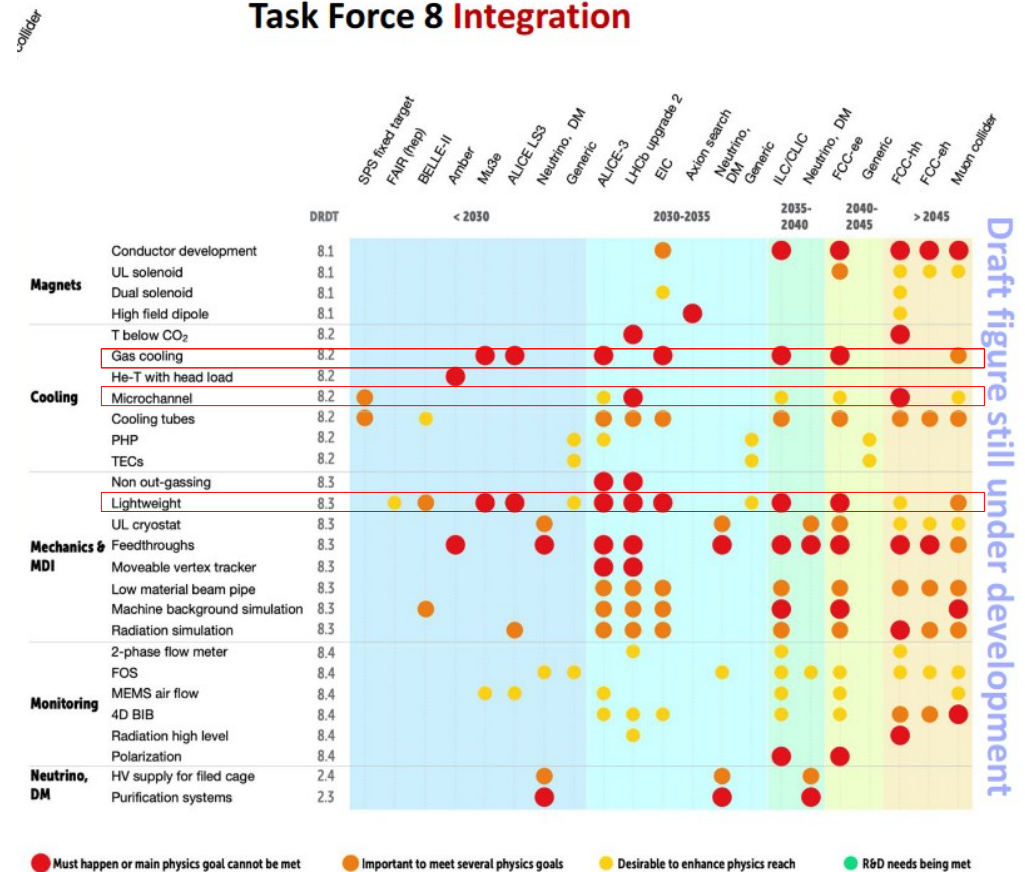
Agreed Working Hypothesis

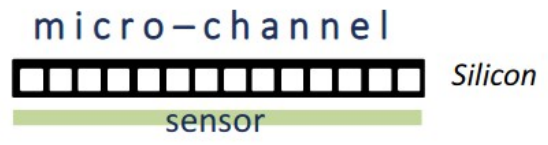
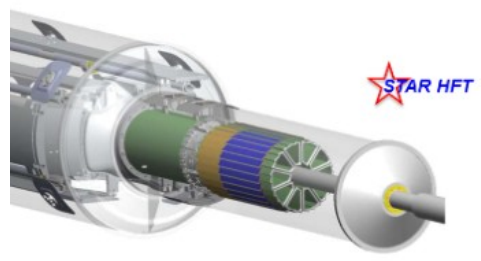
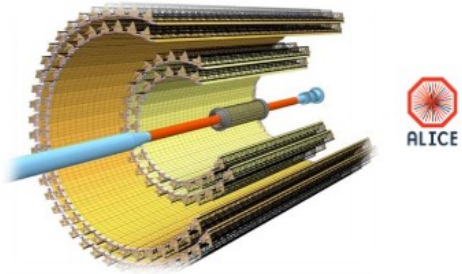
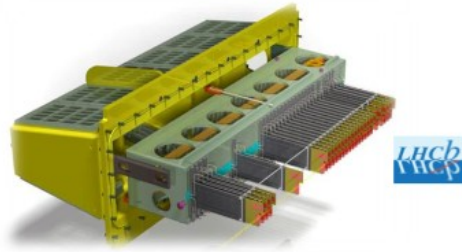


- Funding for “future” projects and “blue sky” R&D is scarce
- Try to use intermediate-timescale projects as stepping stones

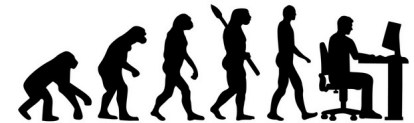
Important efforts in Europe and US to define detector R&D programs for upcoming experiments in particle physics

Cooling and low-mass structures are prominent
In many projects





MCC evolution: integrated cooling



Hybrid pixel detector &
micro-channel cooling plate



Monolithic CMOS detector



Monolithic CMOS detector
with integrated micro-channels

Integrated detector design with support and cooling

- AIDA2020: production and characterization of several Silicon structures with/without micro-channels
- IFIC: Design of Belle 2 PXD upgrade, with U. Bonn, IJCLab, QM
proto-typing self-supporting ladders with IZM
FE simulation and setup to characterize cooling performance
- CNM: Development of in-house “post-processing” capacity
anodic and eutectic bonding compatible with metal
wafer-level integration of micro-channels in CMOS sensors

Staff scientists at IFIC and CNM are guaranteed (but busy)
Difficulties finding/keeping clean room staff and mechanical engineers

- IFIC: Carlos Orero Canet starts in April 2024
- continuity beyond AIDAinnova ensured with regional funding
- IFIC: possible master project student from Oregon this summer
- CNM: lost clean-room technician, hiring replacement

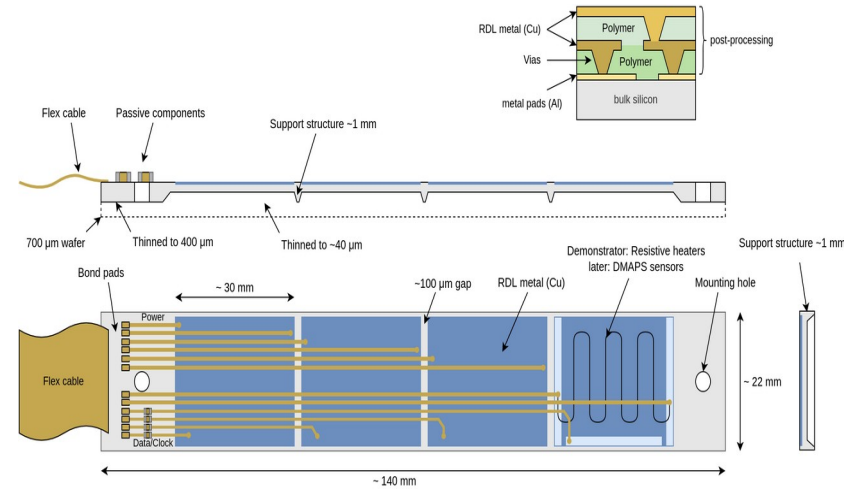
iVTX Inner Layer Concept

All-silicon module < 0.15 % X_0

4 contiguous sensors diced as a block from the wafer
 Redistribution layer for interconnection
 Heterogeneous thinning for thinness & stiffness

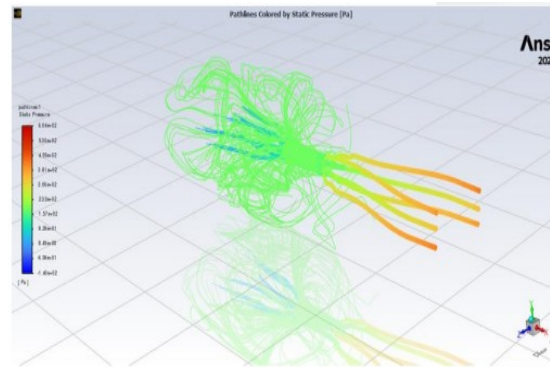
Prototyping

First real-size ladders at IZM-Berlin with dummy Si
 True iVTX geometry available



Simulation on cooling

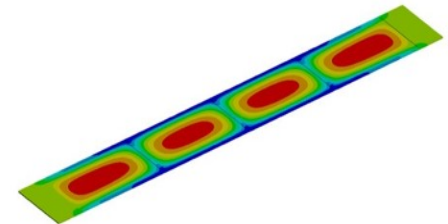
Dry air cooling 15°C
 Assume 200 mW/cm²



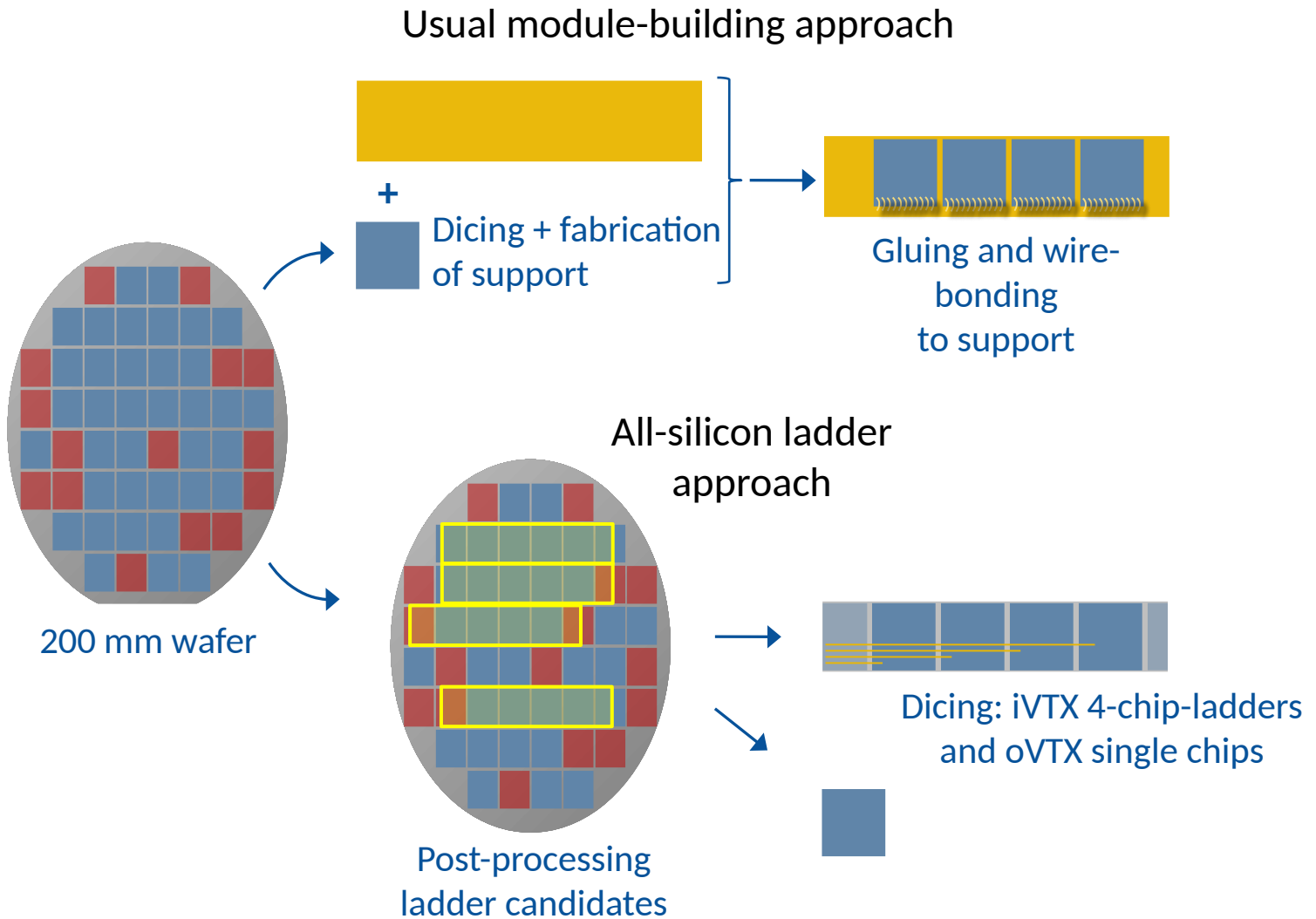
B: Coques
 Type: Temperature
 Unit: °C
 Temp: 1 s
 03/06/2022 10:57

19,838 Max
 19,723
 19,609
 19,494
 19,38
 19,265
 19,151
 19,036
 18,922
 18,807 Min

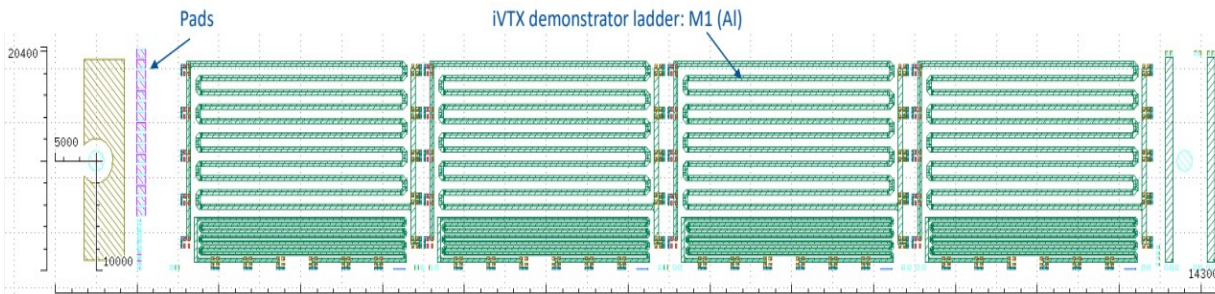
$T_{MAX} \sim 20^\circ C$
 $\Delta T < 5^\circ C$



All Silicon CMOS Ladders



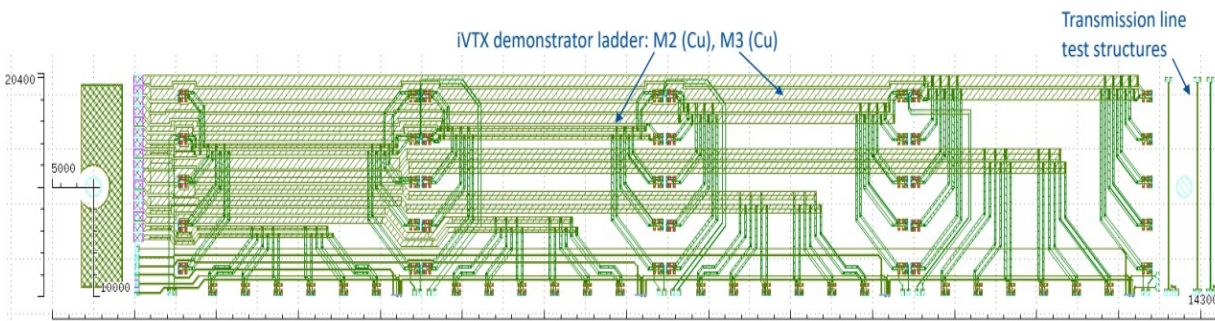
iVTX Ladder Demonstrator



Metal system:

- Resistive heaters: 1.5 μm Al (M1)
- 2 RDL metal layers: 3 μm Cu (M2, M3)
- Top metal finish: NiAu (M4)

Wirebonding, SMD soldering

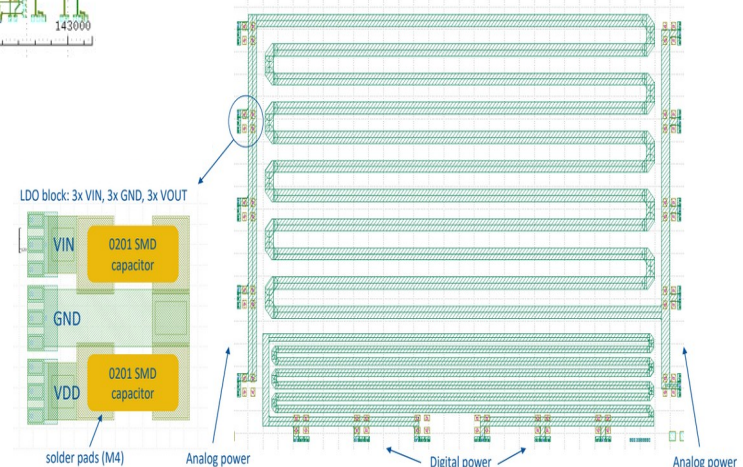
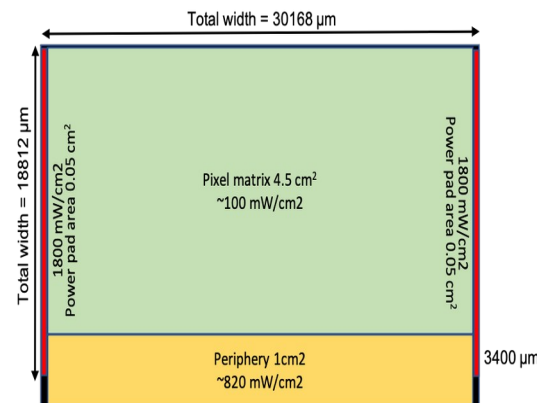


Final ladder dimension: 143 x 20.4 mm^2

Dummy heaters: 30 x 20 mm^2

Prepared for 1.7 mm mounting hole

Characterization of electrical, mechanical and thermal performance of iVTX ladders

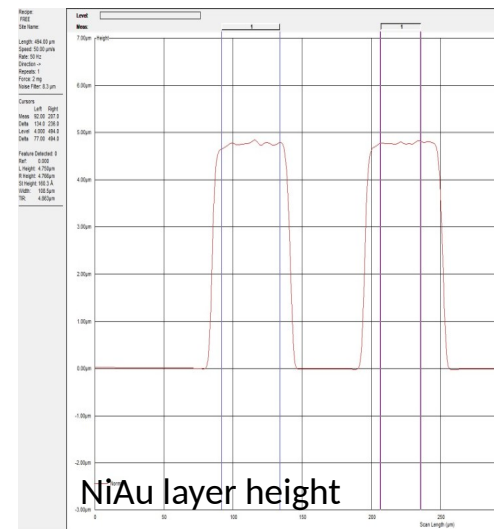
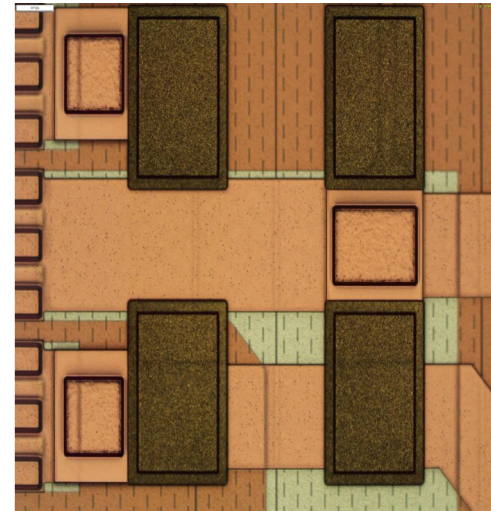
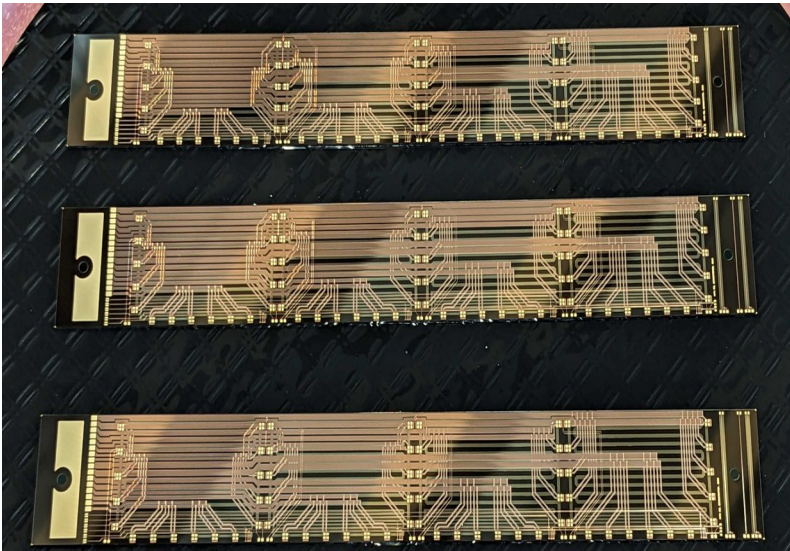


iVTX Ladder Demonstrator

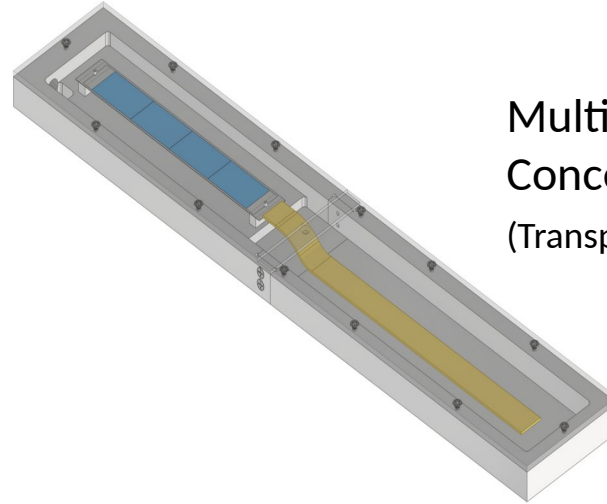
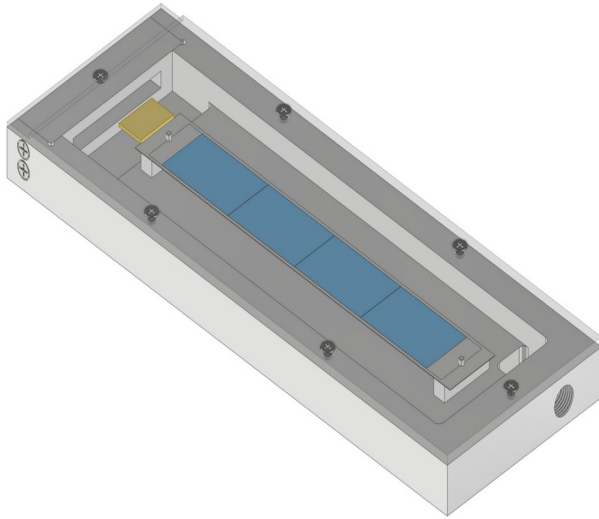
First demonstrators arrived at IFIC:
8 Wafers (725 μm , 400 μm , 300 μm)

Production at IZM finished smoothly

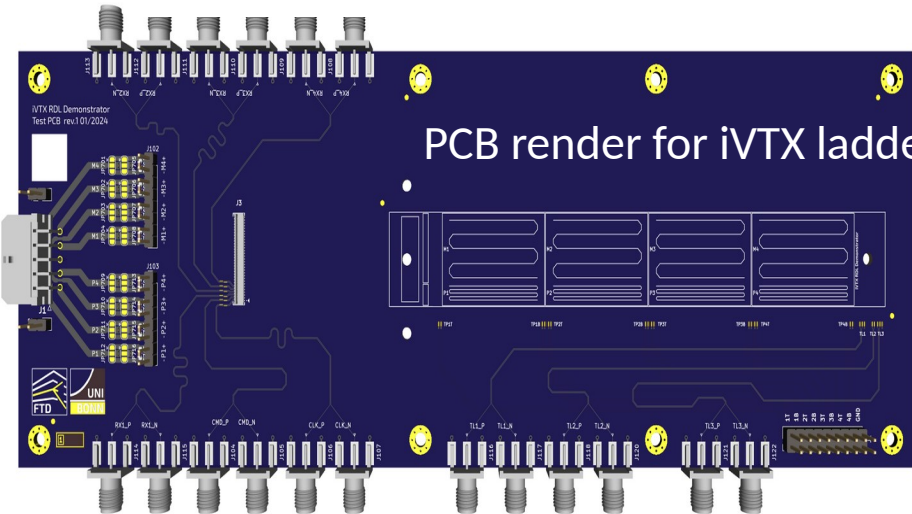
Characterization starting



iVTX Ladder Tests



Multiuse Ladder Box
Concepts
(Transportation, bonding, tests)

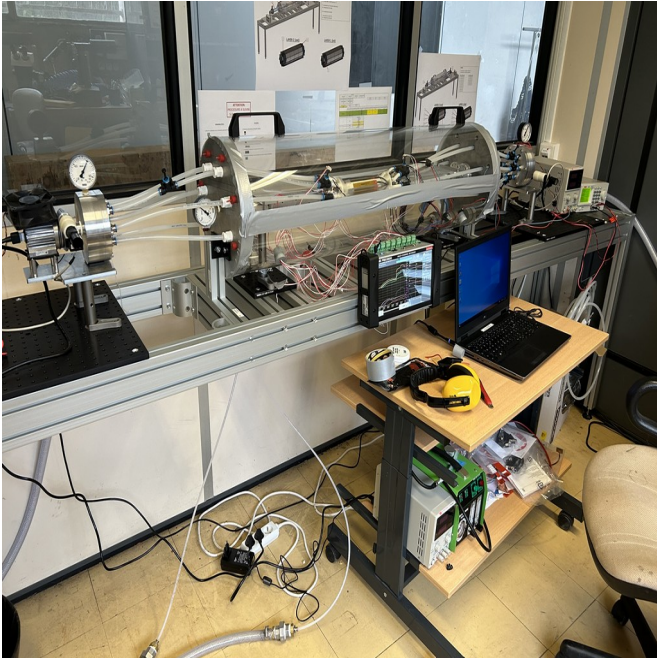


Configurable power routing and test points for I^*R drop measurements

SMA connection for data lanes and TDR measurements

Also preparing a PCB mockup of the ladder to practice soldering etc

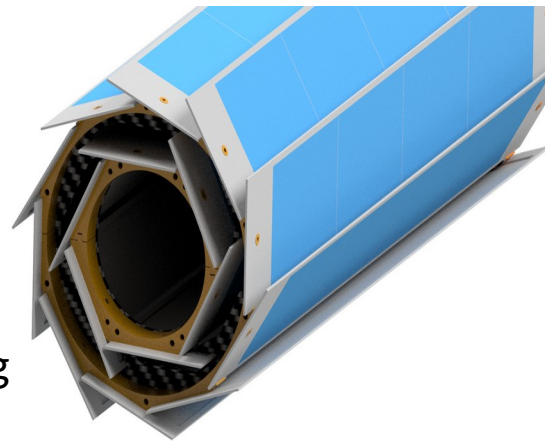
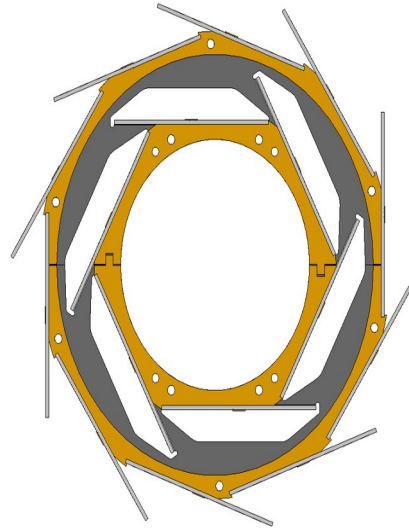
iVTX Integration and Cooling



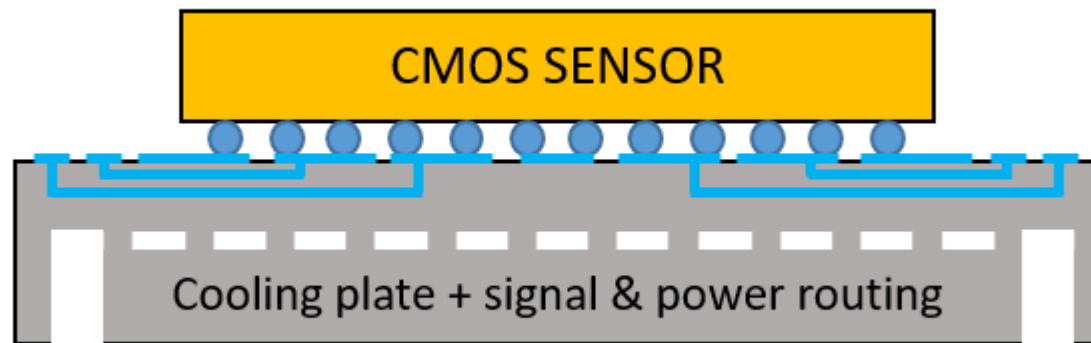
iVTX wind tunnel to study flow

Air cooling feasibility under study

Next: ladder mounting/service routing

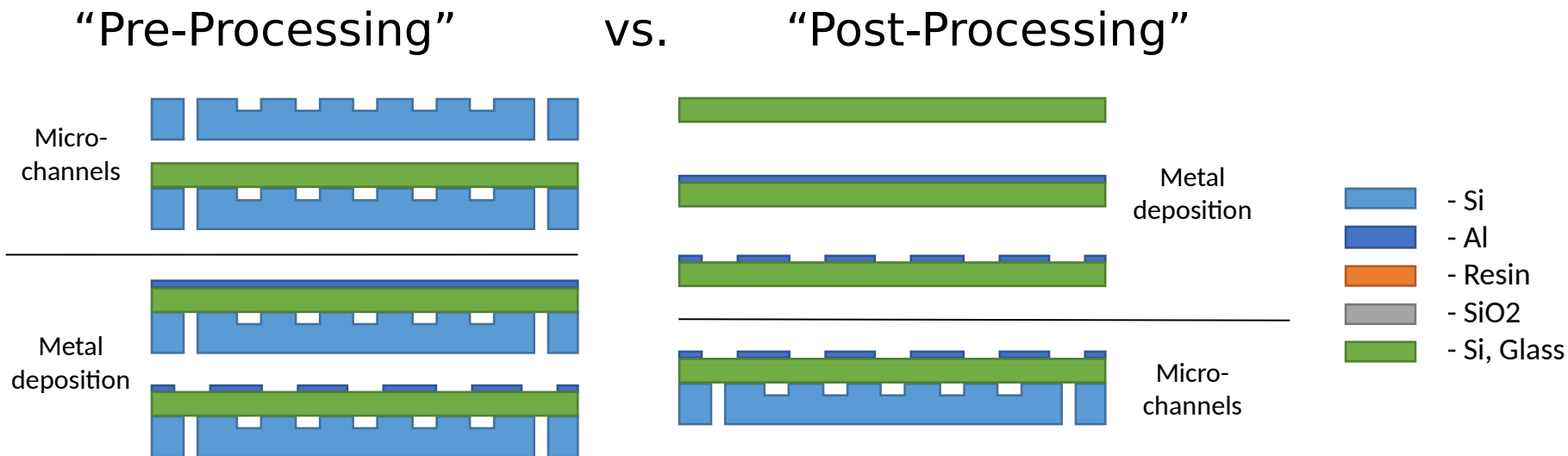


First objective: integration of micro-channels in silicon plates with integrated signal and power routing. **Achieved!!**



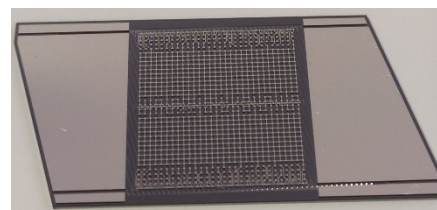
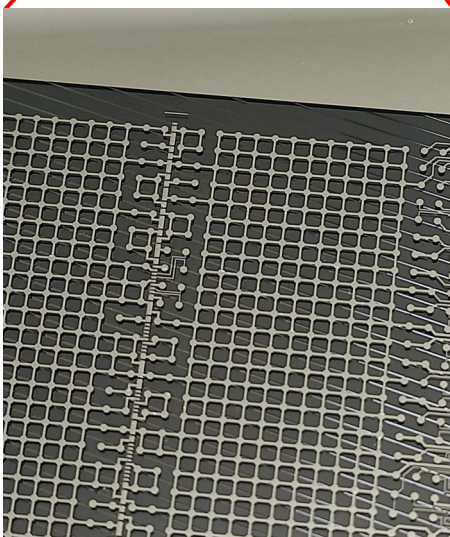
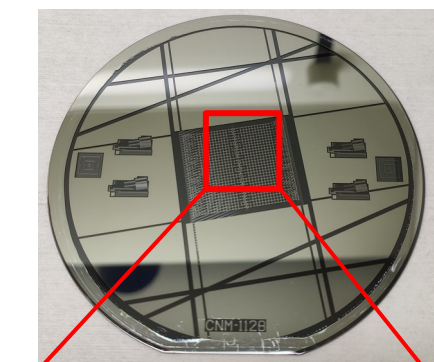
- Technological options

- **Pre-processing:** The microchannels are created first, sealed, and only then the metal is deposited on the assembly and structured with a photolithographic process
- **Post-processing:** The metal is deposited and structured first on a single wafer, then the buried microchannels are created by wafer bonding (at low temperature)

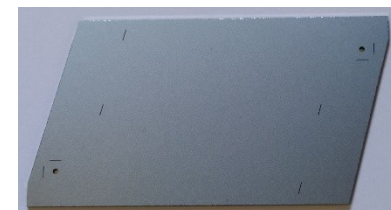


Pre-processing:

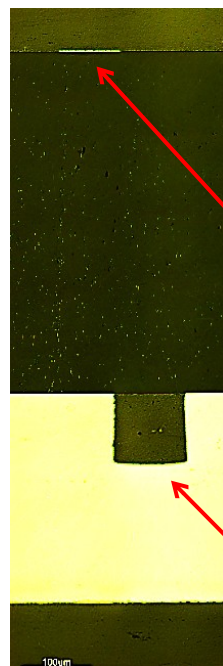
- Successful integration of microchannels in silicon plates with integrated signal and power routing



Front

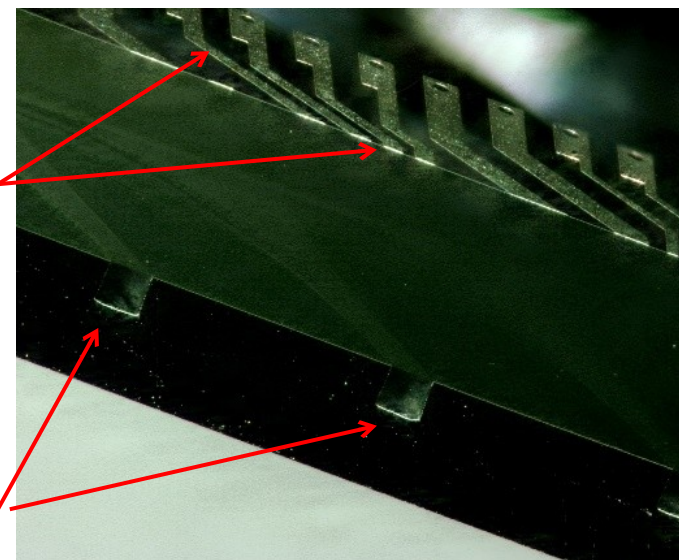


Back

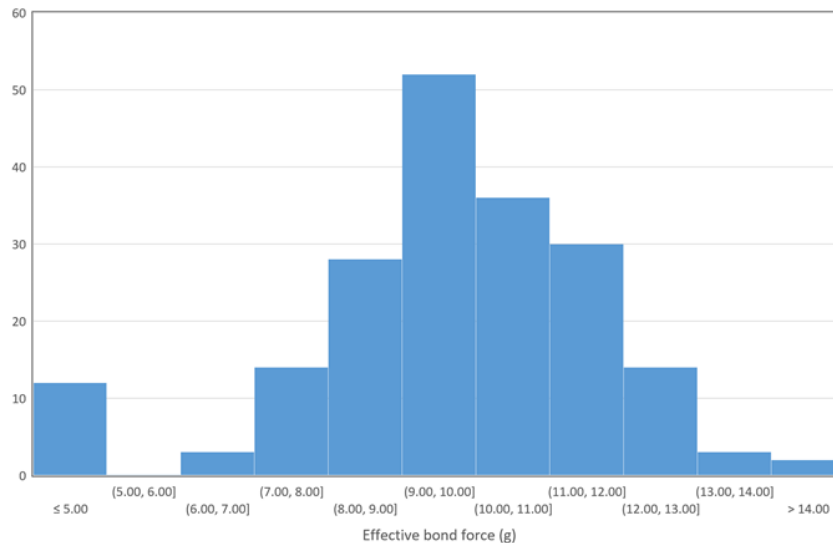
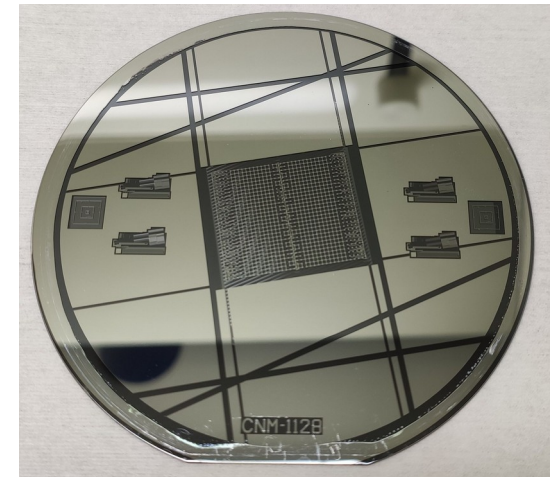


Metal tracks

Microchannels




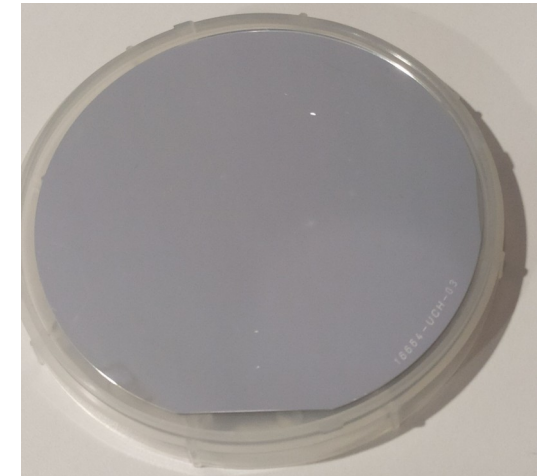
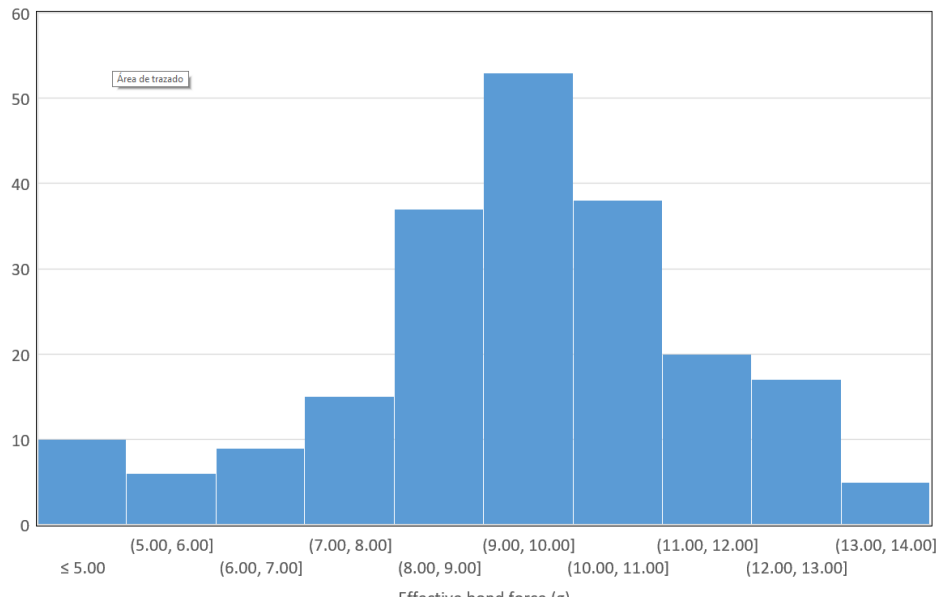
- Tests of the metal system: bondability
 - Hundreds of wire-bonds made and pulled on full assemblies
 - } 25 μm Aluminum wire.
 - Test performed on **Pre-processing** sample
 - } Average bond force obtained: **9.5 \pm 1.3 g**



Post-processing:

- Optimization of metal deposition process
 - Sputtering deposition of the metal at high temperature (350 °C) so the metal is not degraded during the bonding process at high temperature
 - } Better metal test results on blanket wafers
 - Still some localized problems observed in the metal layer
 - } Could be derived from the ion displacement within the glass wafer, inherent to the anodic bonding process
- Process modification to deposit the metal on the Silicon side.
 - Good metal results in blanket wafers, with anodic bonding
 - Final full assemblies with structured metal (signal and power tracks) on-going
 - Good step forward for CMOS integration process !

- Tests of the metal system: bondability
 - Test performed on **Post-processing** blanket assembled sample
 - } Metal on the silicon wafer
 - } Average bond force obtained: $9.6 \pm 1.8 \text{ g}$ 



No degradation of the metal system: technology for integration of embedded microchannels and metal routing demonstrated (pre-processing and post-processing)

Aim: integrate support structures and micro-channel cooling in “large” CMOS ladders for Belle 2 upgrade and Higgs factories

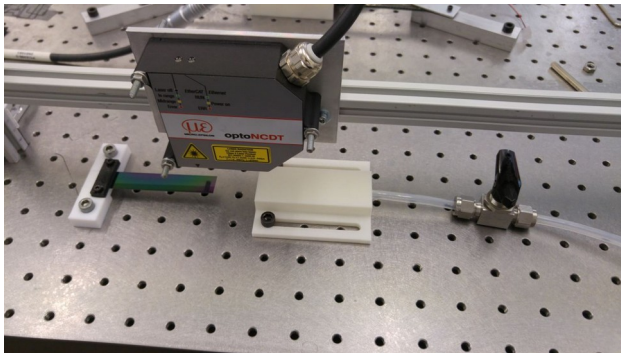
Development of low-temperature bonding compatible with CMOS post-processing ongoing at CNM (M. Ullan), see also L. Andricek for HLL

Integrated micro-channel and metal systems on Silicon: pre-processing and anodic bonding successfully demonstrated. Eutectic bonding soon!

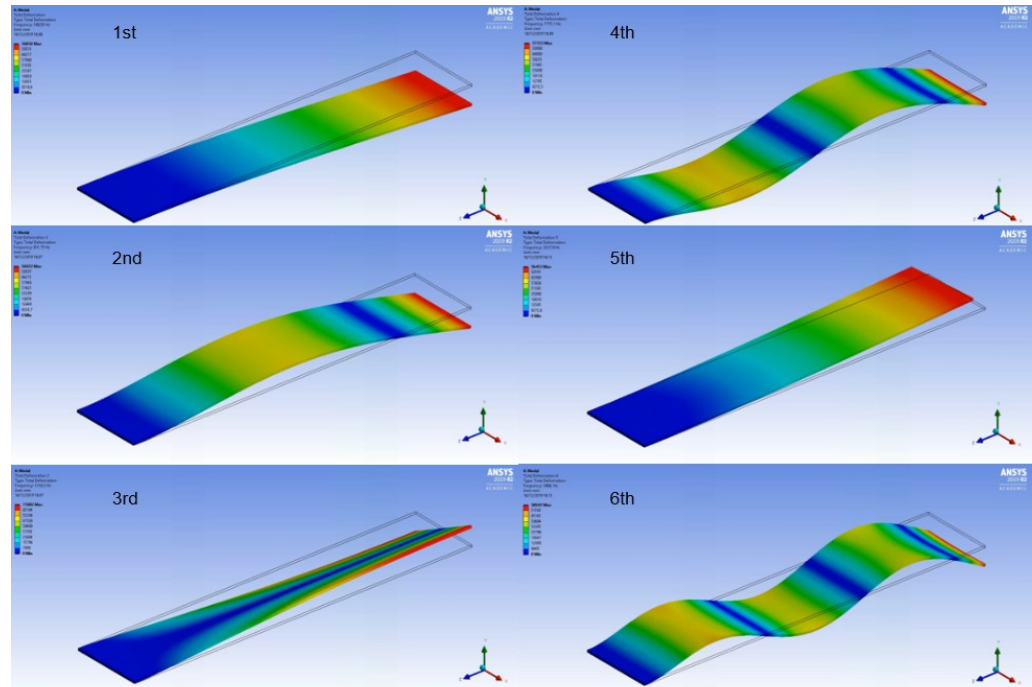
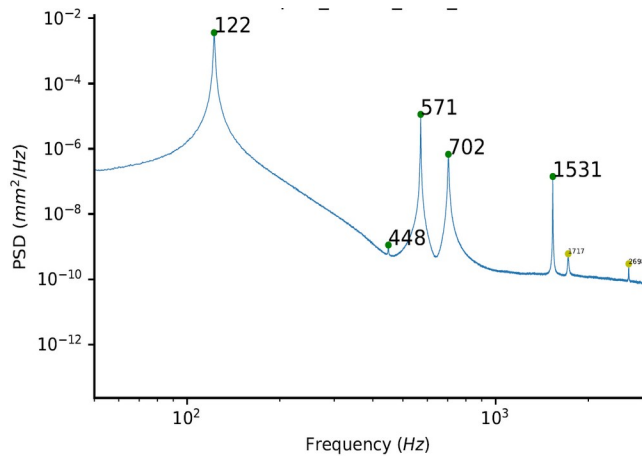
Belle 2 upgrade: extensive FE simulation and prototype measurements to demonstrate gas cooling for very thin ladders. Use simulation to compare to micro-channels.

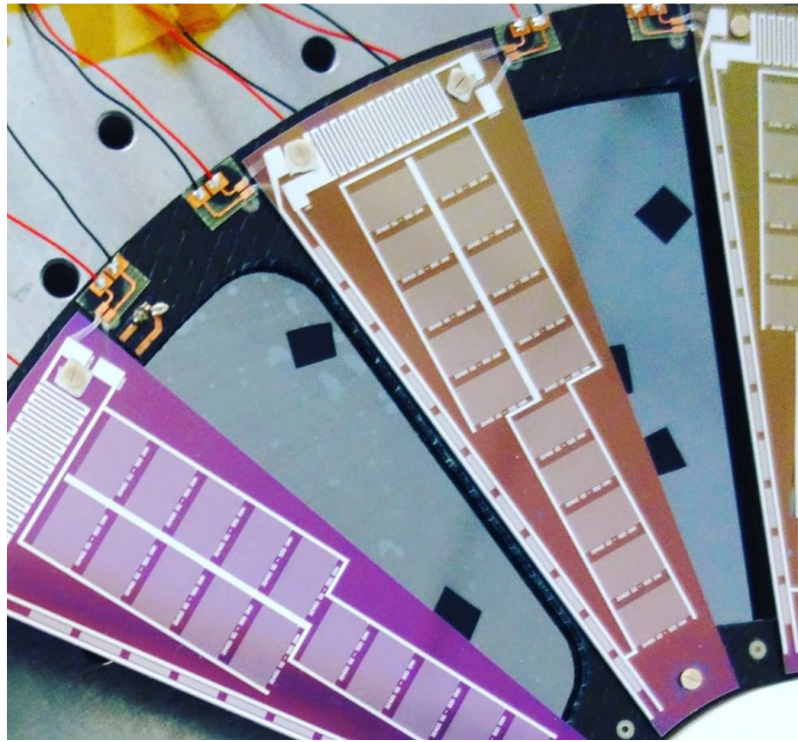
Small steps: mechanical prototypes, simulations & dummy CMOS wafers within AIDAinnova, full demonstrator beyond the timeline of the project.

Multiple silicon structures measured in Oxford and Valencia



Vibration Setup – IFIC Valencia





Master's thesis Yamal Naser Requena

Analytical expressions

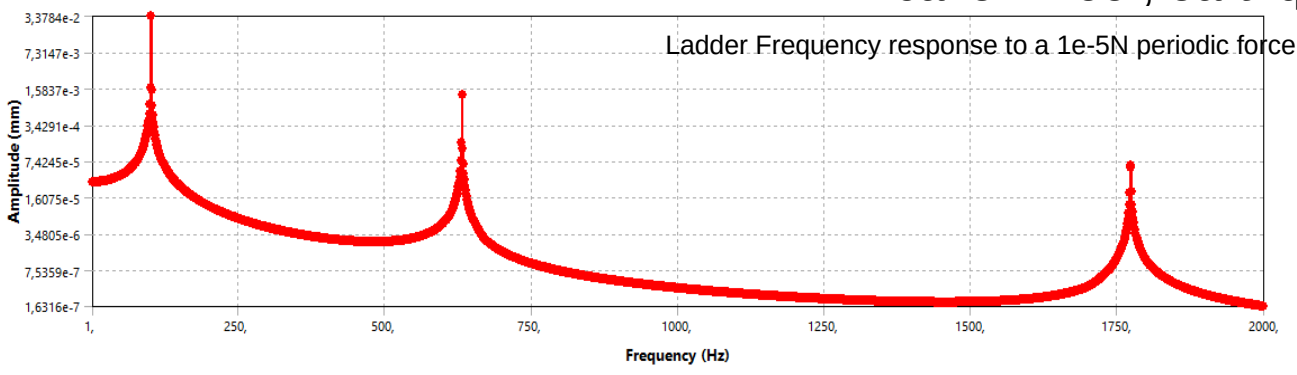
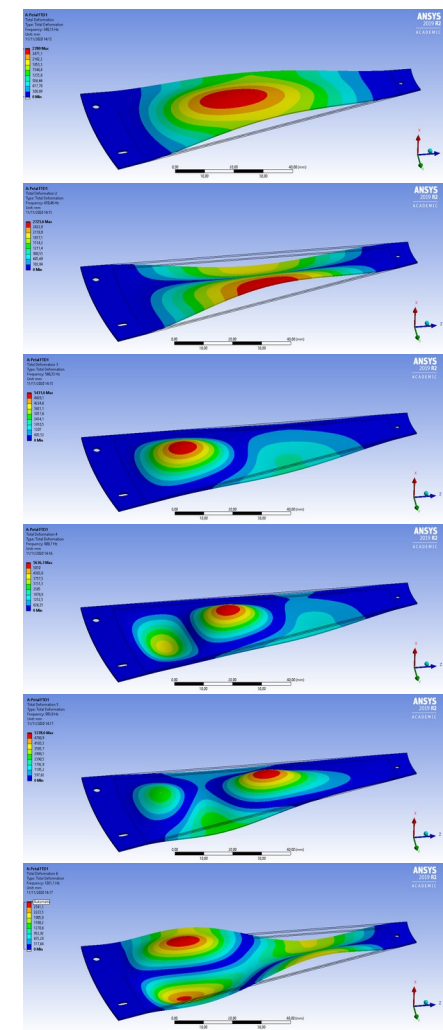
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ANSYS FEA

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Measurements

Extend to more realistic vibration loads (air flow, cavern floor, earthquake)





Grant Agreement No: 101004761

AIDAInnova

Advancement and Innovation for Detectors at Accelerators
Horizon 2020 Research Infrastructures project AIDAINNOVA

MILESTONE REPORT

COMBINED WORKPLAN WITH OBJECTIVES AND TEST DEFINITION FOR ALL TECHNOLOGIES

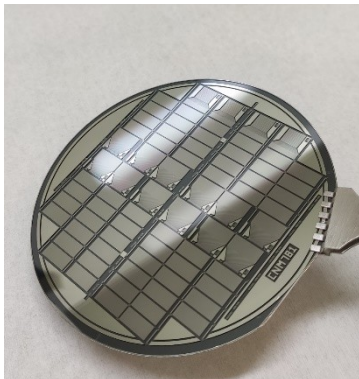
MILESTONE: MS41

Document identifier:	AIDAInnova_MS41.docx
Due date of milestone:	End of Month 11 (February 2022)
Justification for delay:	[if delays occurred]
Report release date:	07/03/2022
Work package:	WP10: Advanced mechanics for tracking and vertex detectors
Lead beneficiary:	CERN
Document status:	Draft

Milestone MS41 with minor delay

Executive summary:

- CNM anodic/eutectic bonding (see M. Ullan)
- HLL direct bonding (see L. Andricek)
- INFN effort on CoolFPGA (see L. Bosi)
- buried channels currently uncovered



- Technology for integration of embedded microchannels and metal routing demonstrated (pre-processing and post-processing)
- Successful fabrication of pre-processing silicon plates with microchannel cooling and integrated signal and power routing
- Good bondability tests results of the metal on the silicon plates with pre- and post-processing

Next steps:

- ❖ Full silicon plates to be finally fabricated with post-processing (on-going)
- ❖ Improve eutectic bonding
- ❖ Thermal and fluidic tests with fabricated silicon plates
- ❖ Working on further integration of microchannel cooling for a full system
 - Full monolithic integration with CMOS sensors
 - Exploring other technological options (microchannels on glass, TSV, ...)